Amendment to the Claims

This listing of claims replaces all prior versions, and listings, of claims in the application.

Listing of claims

- 1. (Cancelled)
- 2. (Currently amended) The A polyamide resin (A) containing an unsaturated group according to Claim 1, wherein obtained by reacting an unsaturated group-containing polyester resin (a) having a terminal anhydride group, which is a compound obtained by reacting a polyol compound (c) containing an unsaturated group with and a tetrabasic acid dianhydride (d), and a compound (b) having two amino groups in a molecule.
- 3. (Original) The polyamide acid resin (A) containing an unsaturated group according to Claim 2, wherein a polyol compound (c) containing an unsaturated group is a compound obtained by reacting a compound (e) having at least two glycidyl groups in a molecule with a monocarboxylic acid (f) having an ethylenic unsaturated group in a molecule.
- 4. (Currently amended) The polyamide acid resin (A) containing an unsaturated group according to Claim 3,

wherein a compound (e) having at least two glycidyl groups in a molecule is (1) a bisphenol-type epoxy resin, (2) a straight chain or cyclic (C2 to C10) aliphatic polyvalent glycidyl ether, provided that the number of a glycidyl group is 2 to 5, and the number of carbon atoms in the case of a cyclic ether is at least 3, (3) a polysulfide type diglycidyl ether, or (4) a biphenol-type diepoxy compound, and in addition, a monocarboxylic acid (f) having an ethylenic unsaturated group in a molecule is a (C3 to C6) aliphatic monocarboxylic acid containing an ethylenic unsaturated group which may be substituted with a phenyl group.

5. (Original) The polyamide acid resin (A) containing an unsaturated group according to Claim 3, wherein a compound (e) having at least two glycidyl groups in a molecule is a compound selected from a group of a phenyl diglycidyl ether compound, a bisphenol-type diepoxy compound, a hydrogenated bisphenol-type diepoxy compound, a halogenated bisphenol-type diepoxy compound, an alicyclic diepoxy compound, an aliphatic diglycidyl ether compound, a polysulfide-type diglycidyl ether compound and a biphenol-type diepoxy compound.

- 6. (Original) The polyamide acid resin (A) containing an unsaturated group according to Claim 4 or Claim 5, wherein a monocarboxylic acid (f) having an ethylenic unsaturated group in a molecule is (meth)acrylic acid or cinnamic acid.
- 7. (Original) The polyamide acid resin (A) containing an unsaturated group according to any one of Claims 2 to 6, wherein a tetrabasic acid dianhydride (d) is a tetrabasic acid dianhydride selected from a group consisting of pyromellitic dianhydride, ethylene glycolbis(anhydrotrimellitate), glycerin bis(anhydrotrimellitate) monoacetate, 1,2,3,4-butanetetracarboxylic dianhydride, 3,3'4,4'-diphenylsulfonetetracarboxylic dianhydride, 3,3'4,4'-benzophenonetetracarboxylic dianhydride, 3,3'4,4'biphenyltetracarboxylic dianhydride, 3,3'4,4'diphenylethertetracarboxylic dianhydride, 2,2-bis(3,4anhydrodicarboxyphenyl) propane, 2,2-bis(3,4-5-(2,5anhydrodicarboxyphenylhexafluoropropane, dioxotetrahydro-3-furanyl)-3-methylcyclohexene-1,2dicarboxylic anhydride, and 3a,4,5,9b-tetrahydro-5-(tetrahydro-2, 4-dioxo-3-furanyl)-naphtho[1,2-c]furan-1,3dione.

- 8. (Currently amended) The polyamide acid resin (A) containing an unsaturated group according to any one of Claims \pm 2 to 7, wherein a compound (b) having two amino groups in a molecule is a compound selected from a group consisting of 4,4-diaminodiphenylmethane, 3,4'-diaminodiphenylmethane, 4,4'-diaminodiphenylether, 3,4'-diaminodiphenylether, 4,4'-diaminodiphenylsulfone, 3,4'-diaminodiphenylsulfone, 4,4'-diaminobenzophenone, and 3,4'-diaminobenzophenone.
- 9. (Currently amended) The polyamide acid resin (A) containing an unsaturated group according to any one of Claims ± 2 to 6, wherein equivalent of an ethylenic unsaturated group of a polyamide acid resin (A) containing an unsaturated group is 300 to 2,000 g/equivalent.
- 10. (Currently amended) The polyamide acid resin (A) containing an unsaturated group according to any one of Claims ± 2 to 8, wherein equivalent of a carboxyl group of a polyamide acid resin (A) containing an unsaturated group is 200 to 1,500 g/equivalent.
- 11. (Currently amended) A method for producing a polyamide

acid resin (A) containing an unsaturated group according to any one of Claims \pm 2 to 10, characterized by reacting a polyol compound (c) containing an unsaturated group, which is a reaction product of a compound (e) having at least two glycidyl groups in a molecule and a monocarboxylic acid (f) having an ethylenic unsaturated group in a molecule, and a tetrabasic acid dianhydride (d) to yield an unsaturated group-containing polyester resin (a) having a terminal anhydride group, which is then reacted with a compound (b) having two amino groups in a molecule.

12. (Original) The method for producing the polyamide acid resin (A) containing an unsaturated group according to Claim 11, wherein a compound (e) having at least two glycidyl groups in a molecule is a bisphenol-type diepoxy biphenol-type diepoxy compound; compound, or а monocarboxylic acid (f) having an ethylenic unsaturated group in molecule is acrylic acid; a tetrabasic acid dianhydride (d) is pyromellitic dianhydride or 3,3',4,4'benzophenone tetracarboxylic dihydride; and a compound (b) having two amino groups in a molecule is 3,4'diaminodiphenyl ether.

13. (Currently amended) A photosensitive resin composition

characterized by containing the polyamide acid resin (A) containing an unsaturated group according to any one of Claims \pm \pm to 12, a crosslinker (B) and a photopolymerization initiator (C).

- 14. (Currently amended) The photosensitive resin composition characterized by containing the polyamide acid resin (A) containing an unsaturated group according to any one of Claims \pm $\underline{2}$ to 12, a crosslinker (B), a photopolymerization initiator (C), and a component (D) to be cured.
- 15. (Original) A cured product of the photosensitive resin composition according to Claim 13 or Claim 14.
- 16. (Original) A substrate having a layer of the cured product according to Claim 15.
- 17. (Original) An article having the substrate according to Claim 16.